

Amendments to the Claims:

The following listing of claims will replace all prior versions, and listings, of claims in the application:

1-11. (Canceled).

12. (Currently Amended) Microstructure comprising an adhesive layer between a substrate and a photo-patternable layer, the adhesive layer being photosensitive, arranged on at least one face of the substrate and being formed by a negative resin comprising at least one polymer of the elastomer family and at least one photo-initiating component, in solution in an ~~aromatic-solvent.~~ solvent;

wherein the adhesive layer has a thickness in the range of 200nm to 10 μ m, and the photo-patternable layer has a thickness in the range of 50 μ m to 200 μ m.

13. (Previously Presented) Microstructure according to claim 12, wherein the polymer is a cyclic polyisoprene in solution in xylene.

14. (Canceled)

15. (Currently Amended) Microstructure according to claim 12, wherein the photo-patternable layer is formed by at least one negative resin ~~of epoxy type.~~ wherein the at least one negative resin is an epoxy resin.

16. (Canceled)

17. (Previously Presented) Microstructure according to claim 12, wherein the substrate is formed by a material selected from the group consisting of silicon, glass and plastics.

18. (Currently Amended) Method of fabrication of a microstructure according to claim 12, further comprising spreading and drying of ~~an the~~ the adhesive layer ~~formed by a negative resin comprising at least one polymer of the elastomer family and at least one photo-~~

~~initiating component, in solution in an aromatic solvent,~~ before deposition of at least one photo-patternable layer of resin.

19. (Previously Presented) Fabrication method according to claim 18, wherein the adhesive layer is exposed through a mask and developed, before deposition of the photo-patternable layer.

20. (Previously Presented) Fabrication method according to claim 18, wherein the adhesive layer and the photo-patternable layer are exposed simultaneously through a mask.

21. (Previously Presented) Fabrication method according to claim 20, wherein the photo-patternable layer and the adhesive layer are developed successively.

22. (Previously Presented) Fabrication method according to claim 18, wherein at least two photo-patternable layers are developed simultaneously, after having been successively deposited and exposed through two different masks.